

WHAT IS CLAIMED IS:

1. A resist stripper which comprises a peroxide and a quaternary ammonium salt.
2. The resist stripper according to Claim 1, wherein the quaternary ammonium salt is at least one member selected from the group consisting of quaternary ammonium hydroxide, a quaternary ammonium carbonate, a quaternary ammonium carboxylate and a quaternary ammonium peroxy-carboxylate.
3. The resist stripper according to Claim 1, wherein the quaternary ammonium salt is quaternary ammonium hydroxide.
4. The resist stripper according to Claim 2, wherein the carboxylic acid in the quaternary ammonium carboxylate is an aromatic carboxylic acid.
5. The resist stripper according to Claim 4, wherein the carboxylic acid in the quaternary ammonium carboxylate is at least one member selected from the group consisting of benzoic acid, salicylic acid and phthalic acid.
6. The resist stripper according to Claim 1, wherein the quaternary ammonium in the quaternary ammonium salt is at least one member selected from the group consisting of a tetraalkyl ammonium, a benzyltrialkyl ammonium and an alkyl-hydroxyalkyl ammonium.
7. The resist stripper according to Claim 1, wherein the quaternary ammonium in the quaternary ammonium salt

is a tetraalkyl ammonium.

8. The resist stripper according to Claim 1, wherein  
the peroxide is at least one member selected from the  
group consisting of hydrogen peroxide, a persulfate, a  
perborate, a percarbonate, an organic peracid and an  
organic hydroperoxide.

9. The resist stripper according to Claim 1, wherein  
the peroxide is hydrogen peroxide.

10. The resist stripper according to Claim 1, wherein

*Svd* the peroxide and the quaternary ammonium salt are  
peroxyhydrate of the quaternary ammonium salt.

11. The resist stripper according to Claim 1, which has  
at least one member selected from the group consisting of  
an amine, a water soluble organic solvent and water added  
to the peroxide and the quaternary ammonium salt.

12. The resist stripper according to Claim 1, which has  
water added to the peroxide and the quaternary ammonium  
salt.

13. The resist stripper according to Claim 1, which has  
water and an amine added to the peroxide and the  
quaternary ammonium salt.

14. The resist stripper according to Claim 1, which has  
water and a water soluble organic solvent added to the  
peroxide and the quaternary ammonium salt.

15. The resist stripper according to Claim 1, which has  
water, an amine and a water soluble organic solvent added  
to the peroxide and the quaternary ammonium salt.

16. The resist stripper according to Claim 11, wherein  
the water soluble organic solvent is at least one member  
selected from the group consisting of a sulfoxide, a  
sulfone, an amide, a lactam, an imidazolidinone, a glycol  
and a glycol ether. A
17. The resist stripper according to Claim 15, wherein  
the water soluble organic solvent is dimethyl sulfoxide.
18. The resist stripper according to Claim 1, for  
stripping of a titanium oxide.
19. The resist stripper according to Claim 1, for  
stripping of a resist or a resist residue remaining after  
development of a photoresist and formation of a circuit.
20. A resist stripper which comprises peroxyhydrate of a  
quaternary ammonium salt.
21. A resist stripper which comprises peroxyhydrate of  
tetramethylammonium hydroxide. A
22. A resist stripper which comprises peroxyhydrate of  
tetraethylammonium hydroxide.

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